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Form PTO-1449 Gauthier & Connors, LLP 225 Franklin Street Boston, MA 02110 Telephone: (617)426-9180 **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**	ATTORNEY DOCKET NO. **MIT.9996** APPLICANT **Gil et al.** FILING DATE **October 2, 2003**	SERIAL NO. **10/677,173** GROUP **1756** EXAMINER **Chacko David, Daborah**

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub-class	Filing Date if Appropriate
	AA						
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FOREIGN PATENT DOCUMENTS

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	AC						
	AD						

OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, etc.)

Examiner Initial		
	AE	"Fox© Flowable Oxide," Dow Corning, Midland, MI, 1996, pp. 1-5.
DCD	AF	H. Namatsu, "Supercritical resist drying for isolated nanoline formation," J. Vac. Sci. Technol. B 19(6), Nov/Dec 2001, pp. 2709-2712.
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EXAMINER /Daborah Chacko-Davis/	**DATE CONSIDERED** 11/09/2006
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